

-6-

with the accompanying drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

5 FIG. 1A through 1D are diagrams to explain conventional steps of fabricating a capacitor element having a via terminal;

FIG. 2 is a cross-sectional view of a semiconductor device substrate according to an embodiment of the present invention;

10 FIG. 3A is an enlarged view of a portion of the semiconductor device substrate shown in FIG. 2;

FIGS. 3A and 3B are cross-sectional views of the semiconductor device substrate with respect to a BB plane and a CC plane, respectively, illustrated in FIG. 2A;

15 FIG. 4 is an enlarged view of an exemplary structure of a via terminal shown in FIG. 3A;

FIG. 5 shows an exemplary structure of a semiconductor device having the semiconductor device substrate shown in FIG. 2;

20 FIGS. 6A through 6D are diagrams to explain fabrication steps of fabricating a semiconductor device substrate according to an embodiment of the present invention;

FIGS. 7A through 7C are diagrams to explain 25 subsequent fabrication steps according to an embodiment of the present invention;

FIGS. 8A through 8C are diagrams to explain subsequent fabrication steps according to an embodiment of the present invention;

30 FIGS. 9A through 9D are diagrams to explain subsequent fabrication steps according to an embodiment of the present invention;

FIGS. 10A through 10D are diagrams to explain

CA  
2/6/06